## **WEST Search History**

Hide Items Restore Clear Cancel

DATE: Wednesday, July 27, 2005

Hide?	<u>Set</u> Name	Query	<u>Hit</u> Count		
DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ					
	L26	91062128	1		
.*	DB=JPAB; PLUR=YES; OP=ADJ				
	L25	JP-91062128-B.did.	0		
	DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ				
	L24	63015710	2		
	L23	6315710	2		
	DB=B	PGPB,USPT,USOC,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ			
	L22	L20 and ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3')))	7		
	L21	L20 and ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution)))	0		
	L20	dainippon screen	17027		
	DB=I	PGPB, USPT, USOC; PLUR = YES; OP = ADJ			
	L19	L18 and 18	17		
	L18	134/902,56R,58R,18,1,33,438/905,906.ccls.	6768		
	DB=I	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ			
	L17	(substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution))	29		
	L16	L15 with (rotat\$3 or spin\$3)	10		
	L15	(substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with (UV or ultraviolet) with ((ozone or 'O.sub.3') adj7 (water or liquid or solution))	69		
	DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ				
	L14	19 same ((substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5))	1		
<b></b>	L13	19 with (substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5)	1		
	DB=B	PGPB,USPT,USOC; PLUR=YES; OP=ADJ			
	L12	19 with (substrate or wafer or semiconductor or workpiece) with (rotat\$5 or spin\$5)	0		
	L11	L10 and 18	6		
	L10	134/902,56R,58R.ccls.	3061		

	DB=	EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	•
	L9	(UV or ultraviolet) with (control\$5 or switch\$3) with power	436
	DB=	PGPB,USPT,USOC; PLUR=YES; OP=ADJ	
	L8	(UV or ultraviolet) with (control\$5 or switch\$3) with power	1099
	DB =	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
	L7	(UV or ultraviolet) with (control\$5 or switch\$3) with power	1535
	L6	L5 same (ozone or 'O.sub.3')	21
$\Box$	L5	((substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3)) same ((UV or ultraviolet) with (control\$5 or switch\$3))	194
	L4	L2 same (ozone or 'O.sub.3')	17
	L3	L2 with (ozone or 'O.sub.3')	12
	L2.	(substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with (UV or ultraviolet) with (control\$5 or switch\$3)	98
	Ll	(substrate or wafer or semiconductor or workpiece) with (clean\$3 or treat\$3 or wash\$3) with ((UV or ultraviolet) adi 10 (control\$5 or switch\$3))	0

## **END OF SEARCH HISTORY**